

Application No.	Applicant(s)	
10/634,904	TAKAHASHI ET AL.	
Examiner	Art Unit	
D. Rutledge	2851	

SEARCHED					
Class	Subclass	Date	Examiner		
355	30, 53, 77	7/23/2004	DR		
118	52,718	7/23/2004	DR		
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INTERFERENCE SEARCHED					
Subclass	Date	Examiner			
53	7/23/2004	DR			

SEARCH NOT (INCLUDING SEARCH		)
	DATE	EXMR
cavity or chamber or compartment; frame or wall or support or housing; build\$3 or construct\$3 or add\$3 or additional, first	7/23/2004	DR
second, embed\$4, air or gas, communicat\$3 or connect\$3, projection adj exposure, lithography, microlithography,	7/23/2004	DR
photolithography, wafer or substrate, mask or reticle, motor, temperature, (sens\$3 or detect\$3 or chang\$3 or adjust\$4,	7/23/2004	DR
chamber or cavity	7/23/2004	DR
Class 29	7/23/2004	DR
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